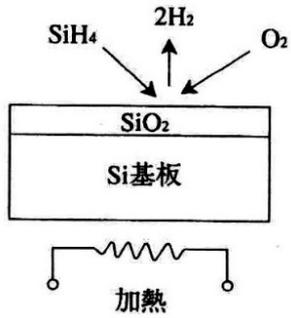
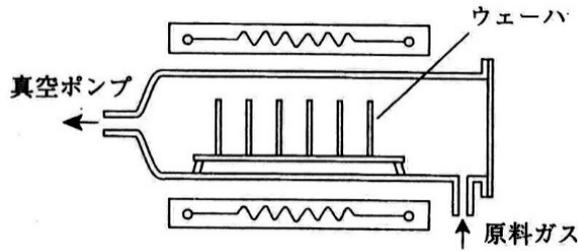


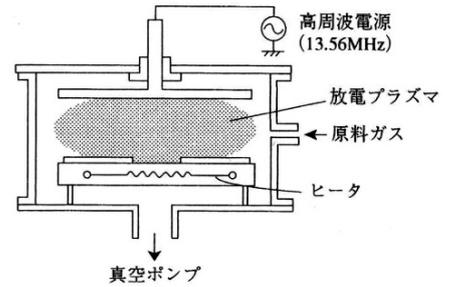
#### 4 化学気相堆積 (CVD) と高周波加熱用電源



化学気相堆積(CVD)の原理



減圧(LP)CVD



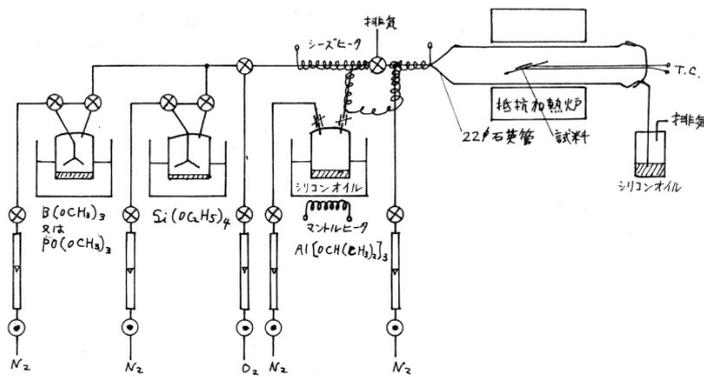
プラズマ CVD



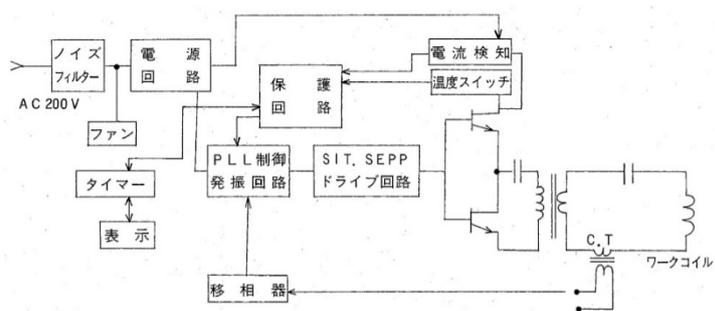
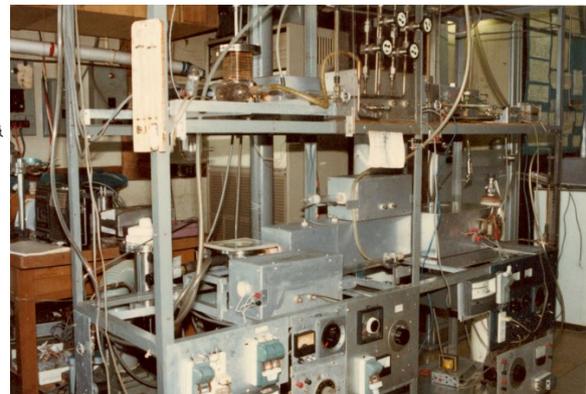
上段高周波加熱 poly Si, SiO<sub>2</sub> CVD  
下段赤外線加熱 Al<sub>2</sub>O<sub>3</sub>, Ta<sub>2</sub>O<sub>5</sub> CVD



低温 SiO<sub>2</sub>CVD 装置 (展示)



TEOS(テトラエトキシシラン)などの液体有機材料による P<sub>2</sub>O<sub>5</sub>-SiO<sub>2</sub>, B<sub>2</sub>O<sub>3</sub>-SiO<sub>2</sub>, Al<sub>2</sub>O<sub>3</sub>-SiO<sub>2</sub> CVD



SIT (静電誘導トランジスタ)を用いた高周波加熱用電源 (トーチン) (展示)